

L Number	Hits	Search Text	DB	Time stamp
-	2	((("20030003407") or ("20030003683")).PN.	USPAT; US-PGPUB	2003/01/25 17:17
-	25384	(resist or photoresist or photopolymer\$7) near3 (develop\$3)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 17:10
-	1494	((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 12:06
-	38757	(Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 12:07
-	58	((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 12:07
-	391	(ultraviolet or uv) with (neon)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/15 10:10
-	57	((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/15 10:11
-	2	((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and (neon same (flow or flowrate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/15 10:11
-	203	((ultraviolet or uv) with (neon)) same (inert or Ar or argon)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/15 10:12
-	51	((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))) and etch\$3	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 15:49
-	1644	(resist or photoresist or photopolymer\$7) and ((develop\$3) adj20 (ultraviolet or uv))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 17:12
-	84	((Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3)) and ((resist or photoresist or photopolymer\$7) and ((develop\$3) adj20 (ultraviolet or uv)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 17:14
-	583	430/328.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/01 14:11
-	16	430/313.cor. and 430/328.cxr.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/22 17:06
-	181	(post adj (expos\$ or develop\$4)) adj20 (ultraviolet or uv)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 18:11
-	49	((post adj (expos\$ or develop\$4)) adj20 (ultraviolet or uv)) and ((Si or silicon or silicone) with (polymer\$7 or photopolymer\$7 or photoresist or resist))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 18:14

21	((post adj (expos\$ or develop\$4)) adj20 (ultraviolet or uv)) and ((Si or silicon or silicone) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) not ((silicon or Si) near3 (wafer or substrate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 18:30
15	((post adj (expos\$ or develop\$4)) adj20 (ultraviolet or uv)) and ((Si or silicon or silicone) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) not ((silicon or Si) near3 (wafer or substrate)) and etch\$3	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 18:30
9	("4751170" "4931351" "5407786" "5427649" "5486424" "5688723" "5707783" "5877075" "6190837").PN.	USPAT	2003/02/01 10:33
567	430/328.ccls. not 430/313.cor.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/01 14:36
1	((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/15 10:14
12	(430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/01 15:03
11	((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) same (flow or flowrate or rate))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/01 15:26
1	((430/328.ccls. not 430/313.cor.) and ((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/01 15:29
329	((resist or photoresist or photopolymer\$7) and ((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/01 15:31
66	((resist or photoresist or photopolymer\$7) and ((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/01 16:50
15	((resist or photoresist or photopolymer\$7) and ((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/01 15:36
51	((resist or photoresist or photopolymer\$7) and ((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))) not ((resist or photoresist or photopolymer\$7) and ((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/01 16:50

554	(((((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))) not (((430/328.ccls. not 430/313.cor.) and ((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))))))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/14 14:45
1984	430/313,317.ccls. not (430/328.ccls. not 430/313.cor.)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/22 17:12
1	((((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))) and etch\$3) and (Ne)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/15 10:02
1	((((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))) and etch\$3) and neon	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/15 10:02
304	(ultraviolet or uv) with (Ne)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/15 10:10
0	((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and (neon same (flow or flowrate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/15 10:12
83	((ultraviolet or uv) with (Ne)) same (inert or Ar or argon)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/15 10:13
3	((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/15 10:14
1	("6054379").PN.	USPAT; US-PGPUB	2003/02/21 17:30

-	58	((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/21 18:38
-	3	430/313.cor. and 430/328.cxr. and (etch\$3 with chamber)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/22 17:07
-	143	430/313,317.ccls. and (etch\$3 with chamber) not (430/328.ccls. not 430/313.cor.)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/22 17:13
-	101	430/313,317.ccls. and (etch\$3 near3 chamber) not (430/328.ccls. not 430/313.cor.)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/22 17:19
-	2231	(resist or photoresist) same ((ultraviolet or uv) with etch\$3)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/22 17:23
-	175	((resist or photoresist) same ((ultraviolet or uv) with etch\$3)) and 430/313,317,328.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/22 17:22
-	17	(resist or photoresist) same ((ultraviolet or uv) with etch\$3 near2 chamber)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/22 17:23
-	4	250/504R-504H.ccls. and (neon or Ne) with (ultraviolet or uv)	USPAT; US-PGPUB	2003/02/22 19:10